

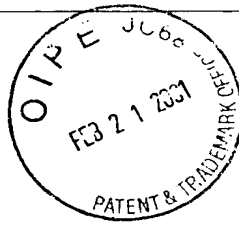
## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:  
Donald L. Yates

Application No.: 09/123,430

Filed: July 28, 1998

For: METHOD OF REDUCING SURFACE  
CONTAMINATION IN  
SEMICONDUCTOR WET-PROCESSING  
VESSELS



Group Art Unit: 2823

Examiner: B. Kebede

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AMENDMENT**BOX NON-FEE AMENDMENT**

Assistant Commissioner for Patents  
Washington, DC 20231

Dear Sir:

In response to the Office Action dated November 21, 2000 (Paper No. 15),  
please amend the above-identified U.S. Patent application as follows:

IN THE CLAIMS:

Please add the following new claims:

-- 48. (new) A method for removing contaminants from a semiconductor  
processing bath for processing semiconductor wafers, said method comprising:

removing an upper portion of a semiconductor processing fluid present in said  
bath from said while said wafers are in said bath, in a manner such that the velocity of said

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